

CHEMICALLY AMPLIFIED RESIST MATERIAL AND PATTERNING
METHOD USING SAME

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ABSTRACT OF THE DISCLOSURE

10 A chemically amplified resist material comprising a
base resin and a photo acid generator having sensitivity
at the wavelength of patterning exposure; wherein, the
chemically amplified resist material further comprising
an activator that generates an acid or a radical by a
treatment other than the patterning exposure. A
15 patterning method using the same is also disclosed.